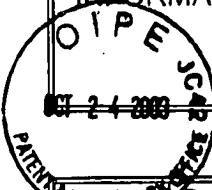


Form PTO-1449 (Modified)	Atty Docket No.	Serial No.
<b>LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</b>	H1553	10/676,911
(Use several sheets if necessary)	Applicant: <b>Amblard</b>	
	Filing Date <b>10/1/03</b>	Group <b>Not yet assigned</b>



## U.S. PATENT DOCUMENTS

## FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Sub-class	Translation	
						Yes	No
P D	TW19990122188	12/99	TW			X*	

\* Abstract only

OTHER ART

Examiner Initial	Author, Title, Date, Pertinent Pages, etc.
P P	Toyoshima, et al, 0.1µm Level Contact Hole Pattern Formation with KrF Lithography by Resolution Enhancement Lithography Assisted by Chemical Shrink (RELACS), IEEE 1998, IEDM 98-333, pp. 12.5.1-12.5.4.
P D	RELACS Resolution Enhancement Lithography Assisted by Chemical Shrink AZ R500, Pure D.I. Water Developable RELACS Coating, Updated on June 28, 2002, Version 05. Clariant Japan K.K., BU Electronic Materials.

EXAMINER	PHUC T. DANG	DATE CONSIDERED	2/12/2004
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**EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Information Disclosure Statement PTO-1449 (Modified)

The identification of any reference is not intended to be, and should not be understood as being, an admission that such publication, in fact, constitutes "prior art" within the meaning of applicable law since, for example, a given reference may have a later effective date than first seems apparent or the reference may have an effective date which can be antedated. The "prior art" status of any reference is a matter to be resolved during prosecution.